

Precursors Having Open Ligands For Ruthenium Containing Films Deposition**ABSTRACT**

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Ruthenium containing precursors for ruthenium containing films deposition comprising a ruthenium precursor selected from the group essentially consisting of: Ru(XOp)(XCp), Ru(XOp)₂, Ru(allyl)₃, RuX(allyl)₂, RuX₂(allyl)₂, Ru(CO)_x(amidinate)_y, Ru(diketonate)₂X₂ Ru(diketonate)₂(amidinate)₂, their derivatives and any mixture thereof.

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